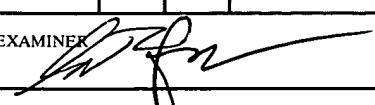


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OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)									
DK	AR		Hiratani, M. et al., "A Conformal Ruthenium Electrode for MIM Capacitors in Gbit DRAMs Using the CVD Technology Based on						
			Oxygen-Controlled Surface Reaction, IEEE, 2000 Symposium on VLSI Technology Digest of Technical Papers, pp. 102-103.						
DK	AS		Kim, Y. et al., "Growth of RuO _x Thin Films by Metal Organic Chemical Vapor Deposition", IEEE 1999, pp. 501-502.						
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